

Abstract

This method provide a method for fabricating a semiconductor device in which waste water generated by a step of processing a semiconductor is filtered to be clean.

5 In the method, removables 12 trapped by a first filter film 10 are used as a second filter film 13, and clogging of the first filter film 10 is prevented, and an external force such as bubbles is applied to the second filter film 13 to maintain filtering capacity. And when removables are mixed

10 with the filtered water, the filtered water is recirculated again to the tank in which the waste water is stored, and after it is checked that a desired inclusion rate has been reached filtration is started again.

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